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# 18<sup>th</sup> International Symposium on Semiconductor Cleaning Science and Technology (SCST18)

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18th International Symposium on Semiconductor Cleaning Science and Technology (SCST18)

**Table of Contents**

Preface	iii
Molecular Dynamics Simulation of Bubble Formation in Confined Water in Si/SiO <sub>2</sub> Nanochannels <i>A. Taghavi Nasrabadi, S. Nishikido, I. Simms, M. Nakamori</i>	3
Deuterium Isotopic Effect on Nanometer-Sized Narrow Spaces Formed by Silicon Walls <i>S. Miyagawa, M. Otsuji, T. Takeda, A. Harumoto, D. Ueda, K. Sawada</i>	7
(Invited) Selective Wet Etching of Semiconductor Materials by Novel Catalyst-assisted Modes <i>K. Arima, J. Li, S. Murase, K. Inagaki</i>	17
Evaluation of Metal Contamination Behavior on Silicon Wafer Surfaces Rinsed with Deionized Water Containing pg/L-Level Impurities <i>K. Tsutano, T. Mawaki, Y. Shirai, R. Kuroda</i>	27
Direct Determination of Metallic Contamination on and in Wafers Using Laser Ablation Inductively Coupled Plasma Mass Spectrometry <i>K. Kawabata, T. Ichinose, K. Suzuki</i>	35
Quantitative Modelling of Residual Molecular Contamination in Low-Pressure Processing Environments <i>P. W. Mertens</i>	51
(Invited) Particles Removal on Challenging Surfaces <i>P. Garnier, H. Galbes</i>	61
Surface Damage by Physical Cleans during Semiconductors Manufacturing <i>P. Garnier, H. Galbes, L. Viravaux</i>	73

Evaluating the Removal of Polystyrene Latex Particles Using the Quartz Transducer Ultrasonic Cleaners in the Megahertz Frequency Range <i>Y. Seike, R. Takagi, T. Hikita, Y. Honda, N. Taoka, Y. Ichino, T. Mori</i>	83
Study of Chemical-Physical Cleaning Technologies for Better Particle Removal Trapped on the Crystal Defects of 4H-SiC <i>G. R. Ha, Y. J. Ra, Y. Gye, J. Park, T. G. Kim, J. Lee, J. Yang, T. U. Kim</i>	93
Modeling and Optimization of Wet ALE Process <i>D. Bassett, K. Abel</i>	101
Investigating the Role of Fluid Dynamics on Cut Width Accuracy in Wet Bevel Cleaning Techniques <i>R. Dong, A. Fujita, D. Bassett, K. Shinohara, S. Takahashi, I. Simms</i>	111
Rate Equation for TiN Etching in Dilute H <sub>2</sub> O <sub>2</sub> <i>D. Ueda, A. Harumoto</i>	117
Extreme Chemical Reduction on Photoresist Stripping Process by Using Sulfuric Acid Ozone Mixture in Liquid Film <i>T. J. Lin, Y. Yamaguchi, S. Shibata, K. Tamura, N. Fujiwara, M. Inaba</i>	125
(Digital Presentation) Investigation of Nanoconfined Wet Etching Mechanism Using MD Simulation <i>Y. Yoshida, T. Nakano, S. Kumari, S. Hu, P. D'elia</i>	133
Author Index	141